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Sheet 1 of 1

Subst. Form PTO-1449 SEP 0 4 2001

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

*(Use several sheets if necessary)*

| Docket Number (Optional) | Application Number |
|---|---|
| 100.718.124 | 09/722,400 |
| **Applicant** Tianhong Zhang and John K. Lee | |
| **Filing Date** November 27, 2000 | **Group Art Unit** 1756 |

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| EXAMINER | DATE CONSIDERED |
|---|---|
| Mohamedulla | 1/24/03 |

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